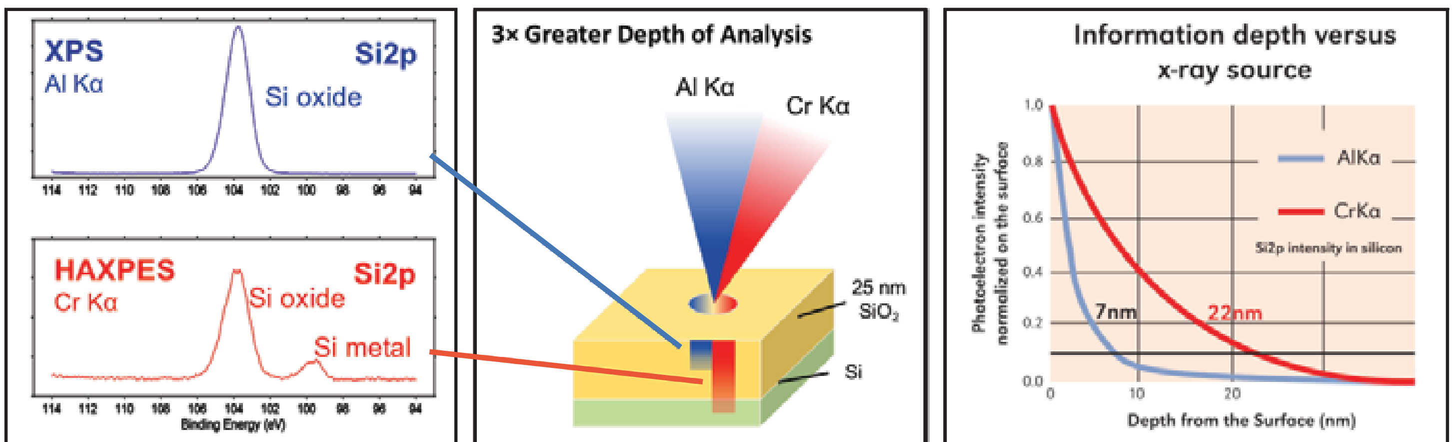
PHYSICAL ELECTRONICS
A DIVISION OF ULVAC-PHI

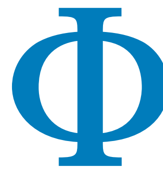
PHI
Quantes
XPS/HAXPES Scanning Microprobe

- Patented XPS/HAXPES scanning microprobe technology
- In-situ analysis using soft (XPS) and hard (HAXPES) X-rays
- Cr X-rays offer 3x greater analysis depth vs. Al X-rays
- Cr X-rays offer access to higher energy core photoelectron peaks
- Patented dual beam charge neutralization for insulator analysis
- High performance spectroscopy and sputter depth profiling
- Fully integrated, high throughput surface analysis

25nm SiO_2 Film on Si Substrate



Al Kα = 1486.6 eV
Cr Kα = 5414.9 eV



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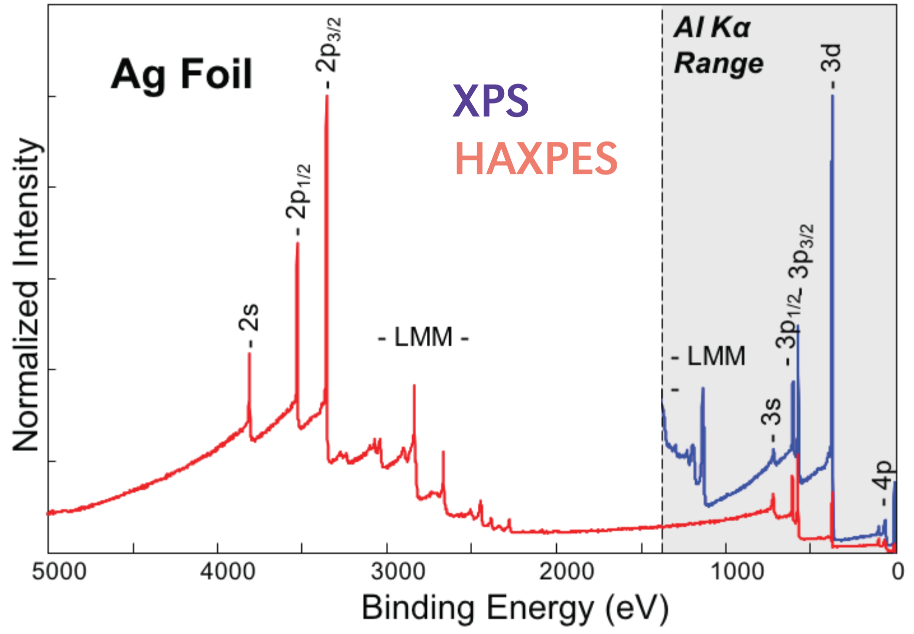
LaB_6 Scanning
Electron Source

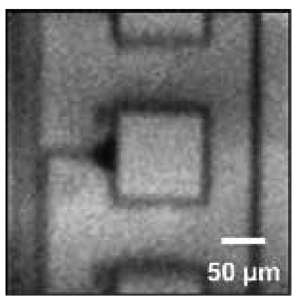
Open Lens
Analyzer Design

Automated
Dual Anode

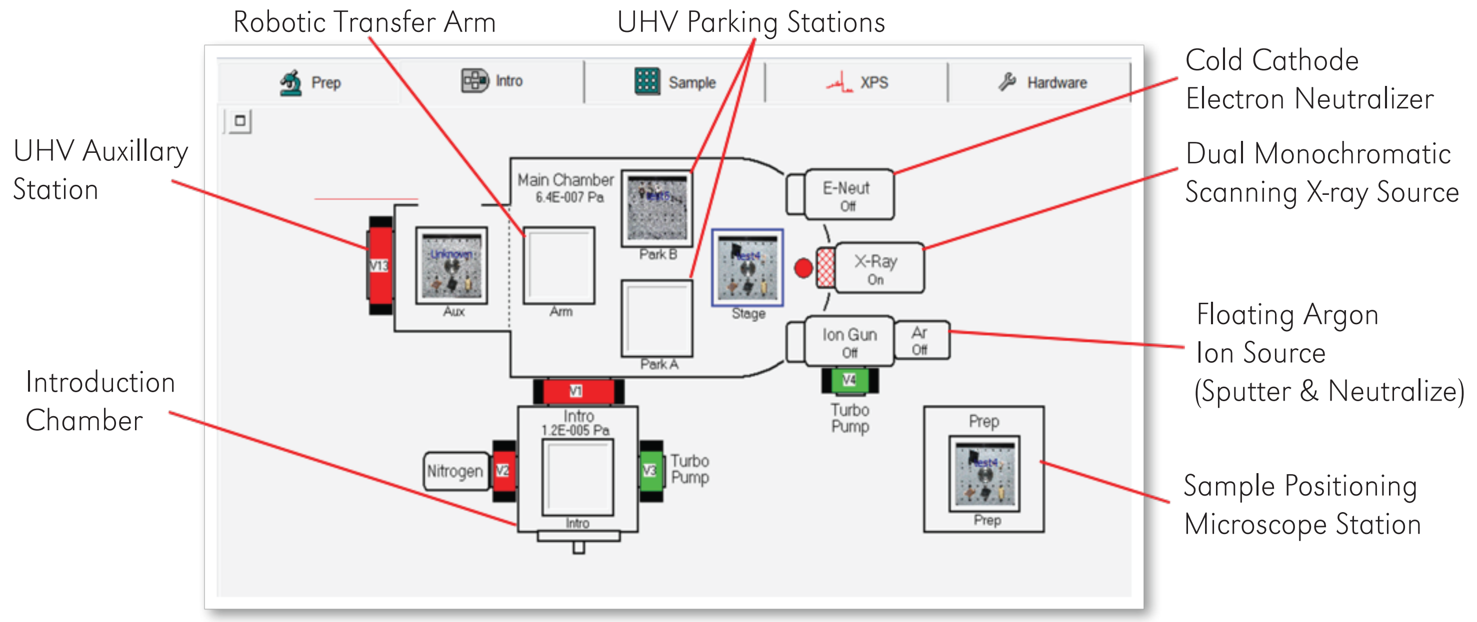
Access to Deeper Core Photoelectron Peaks



Secondary Electron Imaging with Scanning X-rays (SXI)



SmartSoft™ Instrument Control with Intuitive and Simple Workflow



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